

ABSTRACT

A lithographic apparatus includes an illumination system configured to provide a beam of radiation; a support configured to support a patterning device, the patterning device configured to impart the beam with a pattern in its cross-section; a substrate table configured to hold a substrate; a projection system configured to project the patterned beam onto a target portion of the substrate; a measurement system configured to generate an information signal including information about positions of at least one of the patterning device, the substrate, the projection system, and components therein; and a control system configured to control the positions.